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Abstract

A surface treatment for use in the fabrication of MEMS devices

A MEMS fabrication process includes a step in which a surface 4 of a silicon substrate 1 is shaped by etching. The etching process causes surface roughness, but the etched surface 4 of the substrate 1 is smoothed by oxidising it to form a surface oxide layer 5, and then removing the oxide layer 5 by a wet etching process.

[Fig. 3(c)]